

Plasma & Sputtering Sources



envis-ION™ DMPTS

The envis-ION™ Dual Magnetron Pretreatment Source has a wide range of operation for improved adhesion and durability.

FEATURES

- ✓ Flexible mounting options
- ✓ 200+ hours per campaign
- ✓ Hidden electrodes produce minimal contamination
- ✓ Compact design
- ✓ Long electrode life
- ✓ Wide operating pressure (1-40 mTorr)
- ✓ Compatible with other PVD processes
- ✓ Effective source to substrate range of 50-200mm
- ✓ Fast target change

BENEFITS

- ✓ Fits into your existing equipment
- ✓ Fewer process disruptions; longer campaigns
- ✓ Low cost of ownership
- ✓ Promotes film adhesion
- ✓ Reduced chance of substrate damage due to lower ion energies
- ✓ Drives off water vapor and other volatile contaminants from the substrate
- ✓ Wide operating pressure
- ✓ Highly tunable

TECHNICAL DATA

Model	DMPTS
Max Power	5 kW/m
Typical Power	2-4 kW/m
Operating Pressure	1-40 m Torr
Pet Surface Energy at 6.7 m/min	>65 Dynes